



IN 146
AFM/762
SH

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

April 12, 2004

Applicants : Bruce W. Warnes, et al.

For : CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD

Serial No. : 09/950 013 Group: 1762

Filed : Sept. 10, 2001 Examiner: Meeks

Confirmation No. 9221

Mail Stop AF

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

SECOND RESPONSE TO OFFICE ACTION UNDER 37 CFR 1.116

Dear Sir:

Please amend the above application as follows:

IN THE SPECIFICATION

On page 12, replace the second full paragraph with the following paragraph:

The spacer walls 64 form an annular gas manifold 68 at each coating zone 24a, 24b, 24c between the pipe or conduit 18 and walls 64 each of which provides a manifold wall. Each spacer wall 64 opposes or faces the gas discharge openings 62 of the pipe or conduit 18 at that coating zone. Each spacer wall 64 includes first and second sets of circumferentially spaced apart gas flow openings 65 located an equal distance above and below the height of the openings 62 in pipe or conduit 18. Each spacer wall 64 thereby is provided with a plurality of gas flow openings 65 that are out of alignment with the gas discharge openings 62 at each coating zone such that there is no line-of-sight gas flow path from the gas discharge openings 62 to gas flow openings 65 at each coating zone.